Publikationen

Edgar Lodermeier, B. Kunert, R. Ostendorf, J. Wagner, M. Zimprich, S. Liebich, W. Pletschen, Heiko Ranzinger, Günther Benstetter, G. Kaufel, S. Rogowsky, K. Volz, W. Stolz (2012): Characteristics of diode laser structures on silicon substrates based on the Ga(NAsP)/(BGa)(AsP) materials combination. In: Photonics West, San Francisco, CA, USA.

M. Nafría, G. Jaschke, Edgar Lodermeier, X. Aymerich, Heiko Ranzinger, P. Michalowski, Günther Benstetter, M. Porti, L. Wilde, M. Lanza, S. Teichert (2011): Conductivity and Charge Trapping After Electrical Stress in Amorphous and Polycrystalline Al2O3-Based Devices Studied With AFM-Related Techniques. In: IEEE Transactions on Nanotechnology, vol. 10, no. 2, pp. 344-351.

M. Nafría, G. Jaschke, Edgar Lodermeier, X. Aymerich, Heiko Ranzinger, P. Michalowski, Günther Benstetter, M. Porti, L. Wilde, M. Lanza, S. Teichert (2009): Crystallization and silicon diffusion nanoscale effects on the electrical properties of Al2O3 based devices. In: Microelectronic Engineering, vol. 86, no. 7-9, pp. 1921-1924.

M. Schreck, B. Stritzker, Edgar Lodermeier, Günther Benstetter, S. Gsell (2007): Combined AFM-SEM Study of the Diamond Nucleation Layer on Ir(001). In: Diamond and Related Materials, vol. 16, no. 4, pp. 665-670.

M. Nafría, G. Jaschke, Edgar Lodermeier, Heiko Ranzinger, Günther Benstetter, M. Porti, M. Lanza, Werner Frammelsberger (2007): Influence of the manufacturing process on the electrical properties of thin (< 4 nm) Hafnium based high-k stacks observed with CAFM. In: Microelectronics Reliability, vol. 47, no. 9, pp. 1424-1428.

Y. Liu, J. Vancea, Edgar Lodermeier, J. Zhang, Günther Benstetter, D. Liu (2004): Filtered pulsed carbon cathodic arc: plasma and amorphous carbon properties. In: Journal of Applied Physics, vol. 95, pp. 7624-7631. DOI: 10.1063/1. 1753081.

J. Vancea, Edgar Lodermeier, Günther Benstetter, D. Liu (2003): Influence of the incident angle of energetic carbon ions on the properties of tetrahedral amorphous carbon (ta-C) films. In: 16th International Symposium on Plasma Chemistry, Taormina, Italien.

Edgar Lodermeier, Günther Benstetter, D. Liu (2003): Surface roughness, mechanical and tribological properties of ultrathin tetrahedral amorphous carbon coatings from atomic force measurements. In: Thin Solid Films, vol. 436, no. 2, pp. 244-249. DOI: 10.1016/S0040-6090(03)00592-3.

Edgar Lodermeier, I. Akula, I. Dudarchyk, D. Li, T. Ma, Y. Liu, Günther Benstetter (2003): SPM investigation of diamond-like carbon and carbon nitride films. In: Surface & Coatings Technology, vol. 172, no. 2-3, pp. 194-203. DOI: 10.1016 /S0257-8972(03)00338-4.

Edgar Lodermeier, J. Ding, T. Ma, Y. Liu, Günther Benstetter, J. Zhang, X. Chen, D. Liu (2003): Surface and structural properties of ultrathin diamond-like carbon coatings. In: Diamond and Related Materials, vol. 12, pp. 1594-1600. DOI: 10.1016/S0925-9635(03)00248-6.

J. Vancea, Edgar Lodermeier, Günther Benstetter, D. Liu (2003): Influence of the incident angle of energetic carbon ions on the properties of tetrahedral amorphous carbon (ta-C) films. In: Journal of Vacuum Science & Technology A, vol. 21, pp. 1655-1670. DOI: 10.1116/1.1597888.

Edgar Lodermeier, Günther Benstetter, D. Liu: Comparison of Nanoscale Scratch and Wear Resistance of a-C:H, a-C:N and ta-C Fillms. In: International Conference on Plasma Surface Engineering (PSE2002), Garmisch-Partenkirchen.

Edgar Lodermeier, Günther Benstetter, D. Liu: Surface properties and growth of diamond-like carbon films prepared using CVD and PVD methods. In: E-MRS 2004, Strasbourg, Frankreich.

Edgar Lodermeier, Alexander Hofer, B. Knoll, Günther Benstetter, Peter Breitschopf, Werner Frammelsberger: Intermittent Contact Scanning Capacitance Microscopy-First Results. In: Workshop on Scanning Probe Microscopy and Related Techniques, Villach, Österreich.

Edgar Lodermeier, Alexander Hofer, D. Liu, Heiko Ranzinger, Günther Benstetter, Peter Breitschopf, W. Bergbauer, Werner Frammelsberger: Raster-Sonden-Mikroskopie (SPM) in der Fehler- und Zuverlässigkeitsanalytik. In: VDE Fehlermechanismen bei kleinen Geometrien, Grainau.

M. Nafría, G. Jaschke, Edgar Lodermeier, Heiko Ranzinger, Günther Benstetter, M. Porti, M. Lanza, Werner Frammelsberger: Influence of the manufacturing process on the electrical properties of thin (< 4 nm) Hafnium based high-k stacks observed with CAFM. In: 18th European Symposium on Reliability of Electronic Devices, Failure Physics and Analysis (ESREF), Arcachon, Frankreich.